

Title (en)

Alloy sheet for shadow mask and method for manufacturing thereof

Title (de)

Legierung für Schattenmaske und Verfahren zu dessen Herstellung

Title (fr)

Alliage pour masque d'ombre et sa méthode de fabrication

Publication

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Application

EP 96101338 A 19931215

Priority

- EP 93120232 A 19931215
- JP 15288593 A 19930531
- JP 18493893 A 19930727

Abstract (en)

An alloy sheet for making a shadow mask consisting essentially of 34 to 38 wt.% Ni, 0.1 wt.% or less Si, 0.003 wt.% or less B, 0.003 wt.% or less O, less than 0.002 wt.% N, 0.05 to 3 wt.% Cr and the balance being Fe and inevitable impurities; said alloy sheet after annealing before press-forming having 0.2% proof stress of 27.5 kgf/mm² or less; and a gathering degree of 211° plane on a surface of said alloy sheet being 16% or less. A method for manufacturing an alloy sheet for shadow mask comprising the steps of: (a) preparing a hot-rolled sheet containing Fe, Ni and Cr; (b) annealing said hot-rolled sheet in a temperature range of 910 to 990 DEG C; (c) cold-rolling said annealed hot-rolled sheet to produce a cold-rolled sheet; (d) a final recrystallization annealing step of annealing said cold-rolled sheet subjected to the cold-rolling; (e) a finish cold-rolling step of cold-rolling the cold-rolled sheet subjected to the final recrystallization annealing at the cold-rolling reduction ratio in response to an average austenite grain size D (μm) yielded by the final recrystallization annealing, the cold-rolling reduction ratio R (%) satisfying the equations below; $\text{R} = \frac{\ln(D_0/D)}{0.0001(T - 910)}$ $\text{R} = \frac{\ln(D_0/D)}{0.0001(990 - T)}$ (f) a stress relief annealing step of annealing the cold-rolled sheet subjected to the finish cold rolling; (g) a softening annealing step of annealing said cold-rolled sheet subjected to the finish cold-rolling in a temperature range of 700 to less than 800 DEG C for 0.5 to less than 60 min. before press-forming and on conditions satisfying the equation below; $\text{t} = \frac{1}{0.0001(T - 700)}$ where T (DEG C) is the temperature and t (min.) is the time of the annealing.

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Citation (search report)

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- [A] EP 0552800 A1 19930728 - NIPPON KOKAN KK [JP]
- [A] DE 3642205 A1 19880107 - NIPPON MINING CO [JP]
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- [A] DE 3545354 A1 19860703 - NIPPON MINING CO [JP]
- [A] PATENT ABSTRACTS OF JAPAN vol. 015, no. 092 (C - 0811) 6 March 1991 (1991-03-06)
- [A] PATENT ABSTRACTS OF JAPAN vol. 010, no. 296 (C - 377) 8 October 1986 (1986-10-08)

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